

ABSTRACT

**METHOD FOR HEALING DEFECTS IN A LAYER OBTAINED BY
IMPLANTATION THEN DETACHEMENT FROM A SUBSTRATE**

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The invention relates to a method for healing defects in a layer (10) of composition ABO_3 where A consists of at least one element selected from: Li, Na, K, H, Ca, Mg, Ba, Sr, Pb, La, Bi, Y, Dy, Gd, Tb, Ce, Pr, Nd, Sm, Eu, Ho, Zr, Sc, Ag, Tl and B consists of at least one element selected from: Nb, Ta, Sb, Ti, Zr, Sn, Ru, Fe, V, Sc, C, Ga, Al, Si, Mn, Zr, Tl, said layer (10) being obtained by a layer transfer method in which ionic species are implanted into a substrate (100) of composition ABO_3 so as to form a weakened zone delineating said layer, said substrate then being detached along the weakened zone in order to obtain a layer (10) that is detached from the rest of the donor substrate, characterised in that it comprises exposing said layer (10) to a medium (M) containing ions of a constituent element A so as to make said ions penetrate into said transferred layer.

25 Figure 1D